

EUROPEAN PATENT OFFICE

Patent Abstracts of Japan

PUBLICATION NUMBER : 2003128910
PUBLICATION DATE : 08-05-03

APPLICATION DATE : 17-10-01
APPLICATION NUMBER : 2001319788

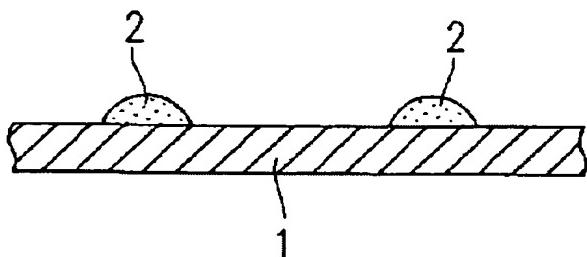
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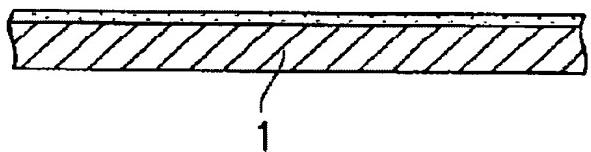
INT.CL. : C08L 75/04 B24B 37/00 C08J 5/14
C08K 5/053 C08L 71/02 C08L 83/04
H01L 21/304

TITLE : POLISHING PAD

(a)



(b)



ABSTRACT : PROBLEM TO BE SOLVED: To provide a polishing pad having increased polishing rate by improving the affinity of the slurry to the polishing pad.

SOLUTION: The polishing pad is made of a polyurethane composition. The polyurethane composition contains a urethane resin copolymerized with a compound having a hydrophilic group and the composition contains a hydrophilicizing agent. The hydrophilicizing agent is one or more compounds selected from 2,4,7,9-tetramethyl-5-decyne-4,7-diol-dipolyoxyethylene ether, 2,4,7,9-tetramethyl-5-decyne-4,7-diol and polymethylalkylsiloxane and the compound having a hydrophilicizing group is one or more compounds selected from ethylene oxide monomer, propylene oxide monomer and ethylene propylene oxide monomer.

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